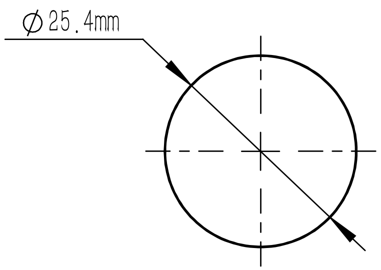

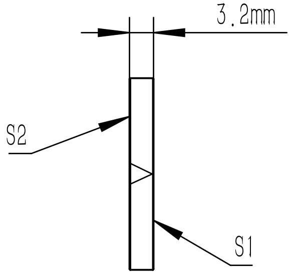

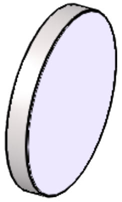

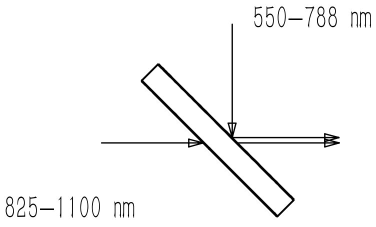

NOTES

1. REFLECTION CUTOFF,TRANSMISSION START WAVELENGTH: 780 nm
2. CLEAR APERTURE: >90%CA
3. SURFACE QUALITY(S1,S2): 40/20(S/D)
4. WAVEFRONT ERROR(RMS): λ/4@633 nm
5. PARALLELISM(S1,S2): <3 arcmin
6. COATING:
    FILTER COATING(S1): Tabs>85%,Tavg>90%@550–788 nm,45° AOI
    Rabs>90%,Ravg>95%@825–1100 nm, 45° AOI
    AR COATING(S2): Rabs<0.8%@550–788 nm, 45° AOI
7. CHAMFER: <0.35 mm,45°

DRAWING PROJECTION			LBTEK			
	NAME	DATE	DM10–780SP			
DRAWN	LZHOU	JUL./30th/24	SHORTWAVE DICHROIC MIRROR ∅25.4 mm×3.2 mm, 780 nm			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	3.6 g	1:1	A